**Reviewer #2:**  
*Manuscript Summary:*  
Overall, the authors provided a detailed procedure, steps need special attention, and results analysis of this technique using sacrificial nanoparticles to remove effect of shot-noise in contact holes. Clear background and rationale are also provided. Therefore, publication is recommended. In addition, the authors may want to consider the following minor suggestions.  
  
*Major Concerns:*  
N/A  
  
*Minor Concerns:*  
1) The authors may want to provide details of Fig 4, like dimensions of GNPs and holes. Moreover, it's not very clear from Fig 4a~c that GNPs didn't move  
after photoresist film reflow. The authors may want to provide more analysis results to support this conclusion.

We agree. The gold NP and hole sizes are 60 nm and 250 nm, respectively. The gold particles do move, about 6 nm during resist reflow based on our analysis of 20 nm particles deposited in 80 nm holes (lines 421-445). We suspect that the RMS displacement of larger particles such as those shown in figure 4 would be smaller due to their stronger binding that should scale as their contact area on the underlying substrate.

2) Line 319 "4c" and line 321 "4d" should be "5c", "5d".

Corrected.  
  
*Additional Comments to Authors:*  
N/A